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TITLE : PHOTOSENSITIVE COMPOSITION AND PHOTOSENSITIVE PLANOGRAPHIC
PRINTING PLATE

ABSTRACT : PROBLEM TO BE SOLVED: To obtain a photosensitive composition excellent in thin line and dot reproducibility, giving a non-image area with no residual color after development and suitable for a positive type photosensitive planographic printing plate excellent in chemical resistance.

SOLUTION: The photosensitive composition contains a quinonediazido compound, a novolak resin and an alkali-soluble resin having ≥ 10 ml/g.cm absorptivity at 436 nm. The alkali-soluble resin is one or more selected from the group consisting of an alkali-soluble polyimide, a copolymer containing N-(3- or 4- carboxyphenyl)maleimide or N-(3- or 4-hydroxyphenyl)maleimide as a copolymerizable monomer and a resin obtained by introducing an azo or quinophthalone yellow dye having its absorption maximum in the range of 400-500 nm into a styrene-maleic anhydride resin. The alkali-soluble resin is contained in a photosensitive layer by 5-30 wt.%.

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